

## **AMENDMENTS TO THE CLAIMS**

This listing of claims will replace all prior versions, and listings, of claims in the application:

### **Listing of Claims**

**Claim 1 (Currently amended):** A plasma treatment apparatus for plasma treating a surface of a substrate in a treatment chamber, comprising:

a base portion which forms a bottom portion of the treatment chamber;

a box shaped member with its lower surface side open and a lower end portion abuts against a base surface on top of the base portion so as to form the treatment chamber;

an electrode section which is fitted on the base portion through an insulator and whose upper surface is exposed in the treatment chamber;

a substrate mounting portion which constitutes an upper portion of the electrode section and whose upper surface is covered with a ceramic;

plasma generating means for generating plasma for plasma treatment in the treatment chamber;

a plurality of bar-shaped ceramic guide members which are disposed on the upper surface of the substrate mounting portion along a substrate transporting direction and are adapted to

guide side end surfaces of the substrate mounted on the substrate mounting portion; and

guide member holding means for holding longitudinal both end portions of the guide members,

wherein the guide member holding means includes:

a pair of fixed members which are fixedly disposed on the base portion in a transverse direction being at a right angle to the substrate transporting direction along outer edges of the substrate mounting portion,

a plurality of supporting members for supporting the both end portions of the guide members, wherein the supporting members are positioned in the substrate transporting direction by the fixed members, and

fitting means for fitting the plurality of supporting members to the fixed members such that the interval in the transverse direction is adjustable,

wherein positioning pins are protruded upwardly on the supporting members, and positioning holes are formed in the guide members, and

wherein the guide members are mounted on the supporting members by fitting the positioning pins upwardly in the positioning holes.

**Claim 2 (Currently amended):** ~~The plasma treatment apparatus according to claim 1~~ A plasma treatment apparatus for plasma treating a surface of a substrate in a treatment chamber, comprising:

a base portion which forms a bottom portion of the treatment chamber;

a box shaped member with its lower surface side open and a lower end portion abuts against a base surface on top of the base portion so as to form the treatment chamber;

an electrode section which is fitted on the base portion through an insulator and whose upper surface is exposed in the treatment chamber;

a substrate mounting portion which constitutes an upper portion of the electrode section and whose upper surface is covered with a ceramic;

plasma generating means for generating plasma for plasma treatment in the treatment chamber;

a plurality of bar-shaped ceramic guide members which are disposed on the upper surface of the substrate mounting portion along a substrate transporting direction and are adapted to guide side end surfaces of the substrate mounted on the substrate mounting portion; and

guide member holding means for holding longitudinal both end portions of the guide members,

wherein the guide member holding means includes:

a pair of fixed members which are fixedly disposed on the base portion in a transverse direction being at a right angle to the substrate transporting direction along outer edges of the substrate mounting portion,

a plurality of supporting members for supporting the both end portions of the guide members, wherein the supporting members are positioned in the substrate transporting direction by the fixed members, and

fitting means for fitting the plurality of supporting members to the fixed members such that the interval in the transverse direction is adjustable,

wherein a plurality of groove portions are formed on an upper surface of the substrate mounting portion along the substrate transporting direction by cutting the substrate mounting surface, and

a projecting portion of a projecting dimension smaller than a depthwise dimension of the groove portions and a notched portion formed by notching a bottom of each of the guide members formed in a shape a rectangular bar with a notching dimension larger than a widthwise dimension of the substrate are formed

continuously in a longitudinal direction on the bottom of each of the rectangular bar-shaped guide members, a side end portion of the substrate mounted on the substrate mounting surface being guided by the notched portion in a state in which the guide member is placed on the substrate mounting surface by advancing the projecting portion into the groove portion.

**Claim 3 (Currently amended):** The plasma treatment apparatus according to claim 1, ~~wherein each of the supporting members has one or more positioning pins and each of the guide members has one or more positioning holes, and wherein the guide members are mounted on the supporting members by fitting the positioning pins in the positioning holes~~ the own weight of the guide members without effecting bolting.